

Form PTO-1449 (REV. 8-83) US Dept. of Commerce PATENT & TRADEMARK OFFICE <b>INFORMATION DISCLOSURE STATEMENT</b> (Use several sheets if necessary)			ATTY DOCKET NO. 118988	APPLICATION NO. New U.S. Application <i>10/191,201</i>		
			APPLICANT(S) Jun HATAKEYAMA et al.			
			FILING DATE March 11, 2004	GROUP		
<b>U.S. PATENT DOCUMENTS</b>						
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS
	1.	US 6,420,088 B1	7/16/2002	ANGELOPOULOS et al.		
	2.	5,294,680	3/15/1994	KNORS et al.		
<b>FOREIGN PATENT DOCUMENTS</b>						
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS
<i>R.A.</i>	3.	JP A 10-69072 w/abstract & transl.	3/10/1998	JAPAN		
	4.	JP B2 7-69611 w/abstract & transl.	7/31/1995	JAPAN		
<i>R.A.</i>	5.	JP A 6-118631 w/abstract & transl.	4/28/1994	JAPAN		
<i>R.A.</i>	6.	JP A 6-118656 w/abstract & transl.	4/28/1994	JAPAN		
<i>R.R.A.</i>	7.	JP A 8-87115 w/abstract & transl.	4/2/1996	JAPAN		
<i>R.A.</i>	8.	JP A 8-179509 w/abstract & transl.	7/12/1996	JAPAN		
	9.	JP B2 3287119 w/abstract & transl.	3/15/2002	JAPAN		
	10.	JP B2 3118887 w/abstract & transl.	10/13/2000	JAPAN		
<i>VIA.</i>	11.	JP A 2000-356854 w/abstract & transl.	12/26/2000	JAPAN		
<i>R.A.</i>	12.	JP A 5-27444 w/abstract & transl.	2/5/1993	JAPAN		
<i>R.A.</i>	13.	JP A 11-60735 w/abstract & transl.	3/5/1999	JAPAN		
<i>R.A.</i>	14.	JP A 6-138664 w/abstract & transl.	5/20/1994	JAPAN		
<i>R.A.</i>	15.	JP A 2001-53068 w/abstract & transl.	2/23/2001	JAPAN		
<i>R.A.</i>	16.	JP A 2001-92122 w/abstract & transl.	4/6/2001	JAPAN		
<i>R.A.</i>	17.	JP A 2001-343752 w/abstract & transl.	12/14/2001	JAPAN		
<i>R.A.</i>	18.	JP A 57-83563 w/abstract	5/25/1982	JAPAN		
<i>R.A.</i>	19.	JP A 57-131250 w/abstract	8/14/1982	JAPAN		
<i>R.A.</i>	20.	JP A 56-129261 w/abstract	10/9/1981	JAPAN		
<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)</b>						
<i>R.A.</i>	21.	Won D. Kim et al.; "Investigation of Hardmask/BARC Materials for 157nm Lithography"; In Microlithographic Techniques in Integrated Circuit Fabrication II, Chris A. Mack, Xiaocong Yuan, Editors, Proceedings of SPIE; Vol. 4226, 2000; pp 93-106				

Date: March 11, 2004*ASH for**9/6/05*

<i>RA</i>	22.	<b>Tom Lynch et al.; "Properties and Performance of Near UV Reflectivity Control Layers"; SPIE; Vol. 2195; pp 225-229</b>
<i>R.A.</i>	23.	<b>Qinghuang Lin et al.; "A High Resolution 248 nm Bilayer Resist"; Part of SPIE Conference of Advances in Resist Technology and Processing XVI, Santa Clara, California; March 1999; SPIE; Vol. 3678; pp 241-250</b>
<i>R.A.</i>	24.	<b>Peter Trefonas et al.; "Organic Antireflective Coatings for 193nm Lithography"; Part of SPIE Conference of Advances in Resist Technology and Processing XVI, Santa Clara, California; March 1999; SPIE; Vol. 3678; pp 702-712</b>
EXAMINER	<i>R. Ashton</i>	
	DATE CONSIDERED <i>9-6-05</i>	
Examiner:	Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	



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Form PTO-14494 (REV. 8-83)		US Dept. of Commerce PATENT & TRADEMARK OFFICE		ATTY DOCKET NO. 118988	APPLICATION NO. 10/797,201	
INFORMATION DISCLOSURE STATEMENT  (Use several sheets if necessary)		APPLICANT(S) Jun HATAKEYAMA et al.				
		FILING DATE March 11, 2004		GROUP		
U.S. PATENT DOCUMENTS						
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS
FOREIGN PATENT DOCUMENTS						
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS
KM	1.	JP B2 7-69611 w/transl. (only)	7/31/1995	JAPAN		
FA	2.	JP B2 3287119 w/transl. (only)	3/15/2002	JAPAN		
R.A.	3.	JP B2 3118887 w/transl. (only)	10/13/2000	JAPAN		
R.A.	4.	JP A 5-27444 w/transl. (only)	2/5/1993	JAPAN		
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)						
EXAMINER <i>Ashton</i>					DATE CONSIDERED <i>9-6-05</i>	
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